

# Measurement Protocols and Handling Instructions

# Graphene Field-Effect Transistor Chip: GFET-S20, S21, S22

### Typical Measurement Configurations

The following explains different electrical measurements that can be performed in GFET-S2X chips.

These devices allow field-effect measurements by simultaneously applying two voltages:

• Source-drain voltage ( $V_{SD}$ ): applied between the two probes (source and drain), while one of them is grounded (see Figure 1a).  $V_{SD}$  enables the transport of charge carriers through the graphene channel, with an associated source-drain current ( $I_{SD}$ ).  $V_{SD}$  can be varied in order to get the desired  $I_{SD}$  outcome (see Figure 1b).

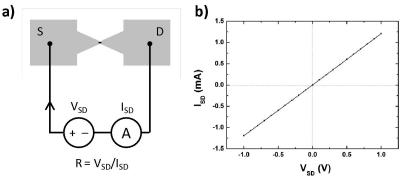


Figure 1. a) Scheme of the 2-probe device, with the corresponding electrical measurement configuration. b) Typical output curve measured at room temperature and vacuum conditions.

• Gate voltage: this voltage can be applied to the silicon (Si) on the substrate (back gating), or to an ionic liquid placed on top of the chip (liquid gating), which will be explained below.

### Back gating

Silicon can be contacted from the top surface by scratching the 90 nm-thick  $SiO_2$  with a diamond pen in one of the chip corners; or alternatively from the underside of the chip, for instance using a probe station chuck. Figure 2 shows a typical transfer curve when a gate voltage  $V_G$  is applied on the Si.

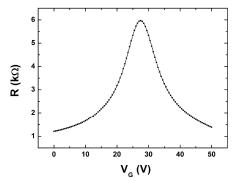


Figure 2. Typical transfer curve of a graphene device, where the device R is measured as a function of the back gate voltage  $V_{g}$ .

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From the data in Figure 2, several parameters associated to the graphene can be calculated.

The resistivity of graphene is usually expressed per thickness unit, i.e. the so-called sheet resistance:

$$R_S = R \frac{W}{L},$$

being W and L the width and length of the graphene channel, respectively. The field-effect mobility ( $\mu_{FE}$ ) can be calculated by using the following equation:

$$\mu_{FE} = g \cdot \frac{1}{C_{SiO2}},$$

## Liquid gating

Alternatively, the charge carrier density of the graphene can be modified by applying a voltage to an ionic liquid in contact with the device channel. This voltage can applied in two ways:

- By an external electrode immersed in the liquid. Ag/AgCl electrodes are widely used for this purpose.
- By the non-encapsulated electrode located at the central area of the chip (see TDS file).

Figure 3 shows a typical transfer curve obtained for liquid gating using the on-chip electrode.

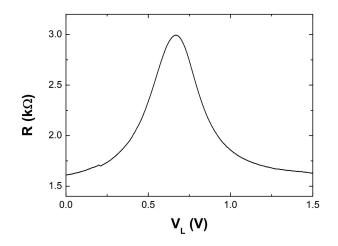


Figure 3. Gating through Phosphate Buffered Saline (PBS, 0.001X) on a S20 chip, using the on-chip Au electrode.



### Doping-reduction treatment

Graphene on SiO<sub>2</sub> is often p-doped after exposure to air due to the adsorption of water molecules and other adsorbates with the effect that the Dirac point is shifted to positive gate voltages and can cause the Dirac voltage to be located out of the recommended gate voltage range, specially during back gate measurements.

Immersing the GFET chip in acetone for at least 12h reduces doping. After that, the chip should be rinsed with IPA, and properly dried with an Ar or  $N_2$  gun. In order to preserve the effectivity of this treatment, electrical characterization via back gating should be carried out in inert atmosphere or vacuum. This treatment is also recommended for liquid gating measurements.

In addition, storage of the chips in a low humidity environment (N $_2$  cabinet, desiccator, or vacuum) is highly recommended.

### Basic handling instructions

The graphene used in our GFETs is high-quality monolayer CVD graphene and highly prone to damage by external factors. To maintain the quality of your devices, we recommend taking the following precautions:

- Be careful when handling the GFET chip that tweezers do not make contact with the device area. Metallic tweezers should be avoided, as they can damage/scratch the chip edges/surface
- Treat the devices as sensitive electronic devices and take precautions against electrostatic discharge
- Ideally store in inert atmosphere or under vacuum in order to minimize adsorption of unknown species from the ambient air
- Do not ultrasonicate the GFET dies
- Do not apply any plasma treatment to the GFET dies
- Do not subject the GFET dies to strongly oxidizing reagents

#### Device lifetime

The devices will remain conductive for a long time (at least 3 months from the moment of purchase). However, mobility variation may happen if the device is stored for a long time, especially if not stored appropriately; see handling instructions section above for recommendations.

If the device is stored in inert atmosphere and is sealed to avoid ambient contamination, mobility variation after 1 month of storage may be up to +/- 15% with respect the pristine mobility. Thus, we recommend a best use date up to 1 month after the devices are purchased.

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